Amendments to the Specification:

Please replace the title as follows:

IMMERSION EXPOSURE APPARATUS AND DEVICE MANUFACTURING METHOD WITH LIQUID DETECTION APPARATUS

Please replace the paragraph beginning on page 4, line 17, with the following rewritten paragraph:

To solve the abovementioned problems, the present invention adopts the following constitution. ~~Furthermore, in the explanation below, each element is assigned a reference symbol in parentheses, which is associated with the constitution of the embodiments depicted in FIG. 1 through FIG. 20; however, the parenthesized reference symbols assigned to the elements are merely illustrative, and the present invention is not limited to those elements.~~

Please replace the paragraph beginning on page 5, line 1, with the following rewritten paragraph:

The exposure apparatus ~~(EX)~~ in accordance with the present invention is an exposure apparatus that exposes a substrate ~~(P)~~ by emitting exposure light ~~(EL)~~ onto the substrate ~~(P)~~ through a projection optical system ~~(PL)~~ and a liquid, ~~(LQ),~~ comprising a detection apparatus ~~(60)~~ that detects whether the liquid ~~(LQ)~~ is present on an object, ~~(P, PST, 300, 400, 500, or the like),~~ which is disposed lower than a front end of the projection optical system. ~~(PL).~~

Please replace the paragraph beginning on page 5, line 16, with the following rewritten paragraph:

The exposure apparatus ~~(EX)~~ in accordance with the present invention is an exposure apparatus that exposes a substrate ~~(P)~~ by emitting exposure light ~~(EL)~~ onto the substrate ~~(P)~~ through a projection optical system ~~(PL)~~ and a liquid, ~~(LQ),~~ comprising a detection apparatus ~~(60)~~ having an emitting portion ~~(61)~~ that emits detection light ~~(La)~~ to an immersion area ~~(AR2)~~ formed between the projection optical system ~~(PL)~~ and an object ~~(P, PST, 300, 400, 500, or the like)~~ disposed on an image plane side of the projection optical system, ~~(PL),~~ and a light receiving portion ~~(62)~~ that is disposed at a predetermined position with respect to the detection light, ~~(La),~~ wherein the detection apparatus obtains at least one of a size and a shape of the immersion area ~~(AR2)~~ based on a light receiving result of the light receiving portion. ~~(62).~~

Please replace the paragraph beginning on page 6, line 12, with the following rewritten paragraph:

The exposure apparatus ~~(EX)~~ in accordance with the present invention is an exposure apparatus that exposes a substrate ~~(P)~~ by emitting exposure light ~~(EL)~~ onto the substrate ~~(P)~~ through a projection optical system ~~(PL)~~ and a liquid, ~~(LQ),~~ comprising a shape detection apparatus ~~(60)~~ that obtains a shape of the liquid ~~(LQ)~~ on an object ~~(P, PST, 300, 400, 500, or the like)~~ movable on an image plane side of the projection optical system. ~~(PL).~~

Please replace the paragraph beginning on page 7, line 1, with the following rewritten paragraph:

The exposure apparatus ~~(EX)~~ in accordance with the present invention is an exposure apparatus that exposes a substrate ~~(P)~~ by emitting exposure light ~~(EL)~~ onto the substrate ~~(P)~~

through a projection optical system ~~(PL)~~ and a liquid, ~~(LQ),~~ comprising a detection apparatus ~~(60)~~ that detects a contact angle of the liquid, ~~(LQ),~~ on an upper surface of a substrate stage ~~(PST)~~ that holds the substrate, ~~(P),~~ with respect to the upper surface of the substrate stage ~~(PST).~~